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Commissioner for Patents, Alexandria, VA 22313-1450.

(Date of Deposit)

Karen Cinq-Mars

(Signature)

5/25/04

(Date)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of : May 18, 2004
Brodsky et al. :
Serial No. 10/709,406 : Examiner:
Filed: 05-03-04 : IBM Corporation
Title: METHOD TO REDUCE PHOTORESIST
PATTERN COLLAPSE BY CONTROLLED
SURFACE MICROROUGHENING : Dept. 18G/Bldg. 300-482
2070 Route 52
Hopewell Junction
New York 12533-6531

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

In compliance with the duty of disclosure under
37 C.F.R. § 1.56 and in accordance with the practice under
37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to
the document listed on the enclosed Form PTO-1449. A copy of the
listed document is also enclosed.

It is respectfully requested that the above information be
considered by the Examiner and that a copy of the enclosed Form
PTO-1449 be returned indicating that such information has been
considered.

Applicants undersigned attorney may be reached by telephone

FIS920030360US1

at (845) 894-6919. All correspondence should continue to be directed to the below listed address.

Respectfully submitted,



Todd M. C. Li
Attorney for Applicants
Registration No.45,554

INTERNATIONAL BUSINESS MACHINES CORPORATION
Intellectual Property Law Department
B/300-482
2070 Route 52
Hopewell Junction, New York 12533
Facsimile: (845) 892-6363

TML/kcm

FIS920030360US1

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| FORM PTO-1449 (Modified) | | | ATTY. DOCKET NO. | SERIAL NO. |
| LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT <i>(Use several sheets if necessary)</i> | | | FIS920030360US1 | <i>10/709,406</i> |
| | | | APPLICANT: BRODSKY ET AL. | |
| | | | FILING DATE: | GROUP: |

REFERENCE DESIGNATION U.S. PATENT DOCUMENTS

| EXAMINER INITIALS | DOCUMENT NUMBER | ISSUED DATE | NAME | CLASS | SUBCLASS | FILING DATE (IF APPRO.) |
|-------------------|-----------------|-------------|------|-------|----------|-------------------------|
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FOREIGN PATENT DOCUMENTS

| | | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUBCLASS | TRANSLATION |
|--|--|-----------------|------|---------|-------|----------|-------------|
| | | | | | | | YES NO |
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OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

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|----|---|--|--|
| CA | S. Lee et al. "New Approach for Pattern Collapse Problem by Increasing Contact Area at Sub-100nm Patterning," Proc. SPIE – The International Society for Optical Engineering, June 2003, pp. 166-174 (Vol. 5039). | | |
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EXAMINER _____ DATE CONSIDERED _____

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance _____ and not considered. Include copy of this form with next communication to applicant.